

# Application News

**Gas Chromatography** 

# No. **G306A**

## Analysis of Sulfur Compounds in Natural Gas by Nexis<sup>™</sup> SCD-2030 According to ASTM D5504

Varying types and amounts of sulfur-containing compounds are present in gaseous hydrocarbon streams. They contribute to the corrosion of facilities and the inhibition of catalytic reactions, leading to the deterioration of product quality.

For these reasons, identifying and quantifying various sulfur compounds then becomes a fundamental requirement in the petrochemical industry from the viewpoints of quality control, safety, and manufacturing process evaluation of products.

In this document, we analyzed sulfur-containing compounds contained in natural gas samples in accordance with ASTM D5504 using gas chromatography with a sulfur chemiluminescence detector (SCD).

The Nexis SCD-2030 provides high selectivity and linearity for sulfur-containing compounds and minimizes the quenching effects of hydrocarbons.

Y. Nagao, S. Li

#### Reagent Information

Three kinds of gaseous samples were prepared in different cylinders as follows:

- Gas ① 14 discrete sulfur compounds diluted in helium at 1ppm(V/V)
- Gas ② Nitrogen
- Gas ③ Natural Gas Standard

A 200 mL gas syringe purchased from GL Science was used for diluting and introducing gases.

Table 1 illustrates the detailed composition of these cylinders.

Gas ① 14 Sulfur Compounds Gas Mixture			Gas ② Nitrogen		
Index	Components	Concentration	Index	Components	Concentration
Balance	Nitrogen	99.999 %	Balance	Nitrogen	99.9995 %
1	Hydrogen sulfide	0.93 ppm			
2	Carbonyl sulfide	0.96 ppm	Gas ③ Natural Gas Standard		
3	Methyl mercaptan	0.99 ppm	Index	Components	Concentration
4	Ethyl mercaptan	0.98 ppm	Balance	Methane	86.595 %
5	Dimethyl sulfide	1.00 ppm	1	Nitrogen	0.10 %
6	Carbon disulfide	1.02 ppm	2	Carbon dioxide	0.30 %
7	2-Propanethiol	0.95 ppm	3	Ethane	8.50 %
8	t-Butanethiol	1.09 ppm	4	Propane	3.50 %
9	1-Propanethiol	1.00 ppm	5	n-Hexane	0.05 %
10	Methyl ethyl sulfide	0.98 ppm	6	Isopentane	0.05 %
11	Thiophene	1.02 ppm	7	n-Pentane	0.05 %
12	Diethyl sulfide	0.99 ppm	8	Isobutane	0.40 %
13	n-Butanethiol	0.95 ppm	9	n-Butane	0.40 %
14	Dimethyl disulfide	0.97 ppm	10	Oxygen	0.06 %

The following document approximately states that the concentration of sulfur compounds in  $\bigcirc$  is 1 ppm.

#### Analysis Method

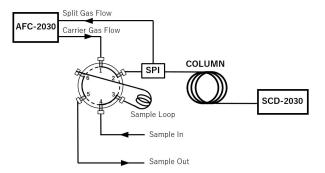


Fig. 1 Schematic of Instrument Configuration

In all evaluations, we used a system configured with a splitter injector (SPI) as a split/splitless vaporization unit. The temperature of the SPI can be controlled independently. Sample introduction was performed via a 6-port gas sample valve interfaced to the SPI.

All sample-paths in the system, such as valves, gastubing, SPI, were Sulfinert<sup>®</sup> treated because volatile sulfur compounds can be highly reactive, absorptive, and adsorptive.

Fig. 1 illustrates a schematic of the instrument configuration.

Table 2 illustrates the details of the analysis method.

## Table 2 Instrument Configuration and Analytical Conditions Instrument Configuration: Instrument Configuration:

Instrument Configuration:						
Main Unit	: Nexis GC-2030					
Valve	: 6-port Valve (Restek)					
Sample Loop Volume	: 1 mL					
Injector	: SPI					
Column	: SH-1 (60 m × 0.53 mm l.D. df=7 μm) *1					
Post Column	: Deactivated Fused Silica Tubing					
<b>-</b>	$(0.3 \text{ m} \times 0.32 \text{ mm})$					
Detector	: SCD-2030					
Analytical Conditions:						
Injector Temp.	∶ 150 °C					
Split Ratio	: 1:9 (10 % to column)					
Carrier Gas	: He					
Carrier Gas Control	: Constant Column Flow mode (6.0 ml/min)					
Column Temp.	: 30 °C (1.5 min) - 10 °C /min - 200 °C (3 min)					
column tempt						
SCD						
Interface Temp	: 200 °C					
Furnace Temp	: 850 ℃					
H <sub>2</sub> flow rate	: 100 ml/min					
N <sub>2</sub> flow rate	: 10 ml/min					
O <sub>2</sub> flow rate	: 12 ml/min					
O₃ flow rate	: 25 ml/min					
*1 P/N: 227-36108-02						

## Linearity and Repeatability Evaluation

ASTM D5504 quantifies the amount of each individual sulfur compound using the external standard method so that the linear response for the sulfur compounds is a primary measurement in the SCD.

We evaluated the linearity of the Nexis SCD-2030 using samples prepared by mixing Gas 1) with Gas 2 to the following concentrations: 50 ppb, 100 ppb, 500 ppb, and 1 ppm(v/v). Fig. 2 illustrates chromatograms of 14 discrete sulfur compound samples. Table 3 illustrates the results of the coefficient of determination (R2) ranging from 50 ppb to 1 ppm and peak area repeatability at 1 ppm (%RSD, n = 5) of each of the sulfur compounds.

The Nexis SCD-2030 is configured with an industry-first horizontal redox cell, which promotes the complete oxidation-reduction reaction of samples by ensuring sufficient reaction area and reaction time in the cell to achieve stable analysis. Use of this configuration lead to excellent linear and stable response for sulfur compounds.

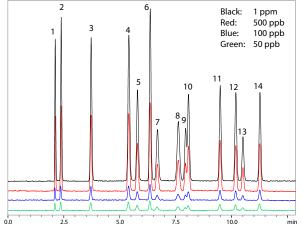


Fig. 2 Chromatograph of 14 Sulfur Compounds Mixture at 50 ppb, 100 ppb, 500 ppb, 1 ppm

Table 3 Linearity and Repeatability Results	
---	--

Index	Components	<b>Linearity</b> (50 ppb, 100 ppb, 500 ppb, 1 ppm)	Repeatability n=5 (1 ppm)
		R <sup>2</sup>	Peak Area RSD%
1	Hydrogen sulfide	0.9999	1.09
2	Carbonyl sulfide	0.9999	0.35
3	Methyl mercaptan	0.9998	0.91
4	Ethyl mercaptan	1.0000	0.90
5	Dimethyl sulfide	0.9998	0.68
6	Carbon disulfide	1.0000	0.29
7	2-Propanethiol	0.9998	1.39
8	t-Butanethiol	0.9999	0.51
9	1-Propanethiol	0.9994	2.15
10	Methyl ethyl sulfide	0.9995	0.68
11	Thiophene	0.9998	1.06
12	Diethyl sulfide	0.9996	0.85
13	n-Butanethiol	0.9997	2.31
14	Dimethyldisulfide	0.9997	0.87

## Selectivity Evaluation

A sulfur chemiluminescence detector can selectively detect sulfur compounds even during analysis of samples with high concentrations of hydrocarbons. Therefore, the ASTM D5504 specifies SCD users to evaluate selectivity and quenching effect of the SCD as a part of the system suitability test.

We used two mixtures of fourteen discrete sulfur compounds at 50 ppb in this evaluation — the Standard Sulfur Mixture and the Natural Gas Sulfur Mixture. The Standard Sulfur Mixture was prepared by diluting Gas 1) with Gas 2) to 50 ppb. The Natural Gas Sulfur Mixture was prepared by diluting Gas ① with Gas ③ to 50 ppb. Fig. 3 shows the chromatogram of Standard Sulfur Mixture, Natural Gas Sulfur Mixture, and Gas (3).

The black line is the chromatogram of the Standard Sulfur Mixture, which illustrates that all fourteen sulfur compounds can be detected in trace-level concentrations. The blue line is the chromatogram for Gas ③ and illustrates no response for all compounds contained in the sulfur-free natural gas. The chromatogram of the Natural Gas Sulfur Mixture, shown by the red line, revealed that all fourteen sulfur compounds were detected in the same manner as the Standard Sulfur Mixture. Therefore, the Nexis SCD-2030 can selectively detect sulfur compounds without being affected by the quenching of hydrocarbons.

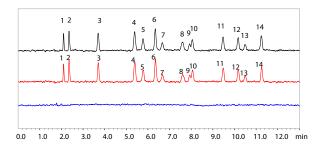


Fig. 3 Chromatogram Comparison of Standard Sulfur Mixture, Natural Gas Sulfur Mixture, and Gas ③

- Black: 14 Discrete Sulfur Compounds In Nitrogen (50 ppb each)
- 14 Discrete Sulfur Compounds In Natural Gas Red: (50 ppb each)
- Blue: Sulfur-free Natural Gas Standard (Chromatogram baseline-shifted for comparison)

Nexis is a trademark of Shimadzu Corporation or its affiliated companies in Japan and/or other countries. Sulfinert is a registered trademark of SilcoTek Corporation.



## For Research Use Only. Not for use in diagnostic procedures. This publication may contain references to products that are not available in your country.

First Edition: Mar. 2019 Revision A: Mar. 2023

Please contact us to check the availability of these products in your country. The content of this publication shall not be reproduced, altered or sold for any commercial purpose without the written approval of Shimadzu. See <u>http://www.shimadzu.com/about/trademarks/index.html</u> for details.

Third party trademarks and trade names may be used in this publication to refer to either the entities or their products/services, whether or not they are used with trademark symbol "TM" or "@".

Shimadzu disclaims any proprietary interest in trademarks and trade names other than its owr

The information contained herein is provided to you "as is" without warranty of any kind including without limitation warranties as to its accuracy or completeness. Shimadzu does not assume any responsibility or liability for any damage, whether direct or indirect, relating to the use of this publication. This publication is based upon the information available to Shimadzu on or before the date of publication, and subject to change ithout notice

Shimadzu Corporation www.shimadzu.com/an/